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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
10/714,909	11/18/2003	Hideo Takagi	032108	4001
38834 75	90 07/28/2005		EXAM	INER
WESTERMAN, HATTORI, DANIELS & ADRIAN, LLP			DANG, PHUC T	
SUITE 700	TICUT AVENUE, NW		ART UNIT	PAPER NUMBER
WASHINGTON, DC 20036			2818	
			DATE MAILED: 07/28/200:	5

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)			
	10/714,909	TAKAGI ET AL.			
Office Action Summary	Examiner	Art Unit			
	PHUC T. DANG	2818			
The MAILING DATE of this communica	tion appears on the cover sheet wit	h the correspondence address			
Period for Reply  A SHORTENED STATUTORY PERIOD FOR THE MAILING DATE OF THIS COMMUNICA  - Extensions of time may be available under the provisions of 3 after SIX (6) MONTHS from the mailing date of this communi  - If the period for reply specified above is less than thirty (30) d  - If NO period for reply is specified above, the maximum statute  - Failure to reply within the set or extended period for reply will Any reply received by the Office later than three months after earned patent term adjustment. See 37 CFR 1.704(b).	ATION.  TOFR 1.136(a). In no event, however, may a recation.  ays, a reply within the statutory minimum of thirty only period will apply and will expire SIX (6) MONION.  by statute, cause the application to become ABIONIONIONIONIONIONIONIONIONIONIONIONIONI	eply be timely filed  (30) days will be considered timely.  THS from the mailing date of this communication.  ANDONED (35 U.S.C. § 133).			
Status					
<ol> <li>Responsive to communication(s) filed on <u>election filed on January 21, 2005</u>.</li> <li>This action is FINAL. 2b) ☐ This action is non-final.</li> <li>Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.</li> </ol>					
Disposition of Claims					
4) ☐ Claim(s) 1-6,8-11,13-16,18,19,21 and 4a) Of the above claim(s) 21 and 22 is/ 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-6,8-11,13-16,18 and 19 is/ar 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction	are withdrawn from consideration.				
Application Papers					
9) The specification is objected to by the E 10) The drawing(s) filed on 18 November 2 Applicant may not request that any objection Replacement drawing sheet(s) including the content of	$2003$ is/are: a) $\square$ accepted or b) $\square$ on to the drawing(s) be held in abeyangle correction is required if the drawing(	ce. See 37 CFR 1.85(a). s) is objected to. See 37 CFR 1.121(d).			
Priority under 35 U.S.C. § 119					
12) △ Acknowledgment is made of a claim for a) △ All b) □ Some * c) □ None of:  1. △ Certified copies of the priority do  2. □ Certified copies of the priority do  3. □ Copies of the certified copies of application from the International	ocuments have been received. Ocuments have been received in Apother the priority documents have been all Bureau (PCT Rule 17.2(a)).	pplication No received in this National Stage			
Attachment(s)  1) Notice of References Cited (PTO-892)  2) Notice of Draftsperson's Patent Drawing Review (PTO-3) Information Disclosure Statement(s) (PTO-1449 or PT Paper No(s)/Mail Date	0-948) Paper No(s	Summary (PTO-413) s)/Mail Date nformal Patent Application (PTO-152) 			

Art Unit: 2818

#### **DETAILED ACTION**

#### Amendment

1. Amendment filed on June 2, 2005 has been acknowledged and considered.

In Amendment, Applicants canceled claims 7, 12, 17 and 20 and amended claims 1 and 13 and withdrawn claims 21-22.

Claims 1-6, 8-11, 13-16, 18-19 and 21-22 are currently pending in the application.

# Response to Arguments

2. Applicant's argument filed on June 2, 2005 with respect to claims 1-6, 8-11, 13-16 and 18-19 have been considered but are most in view of the new ground(s) of rejection.

## **Priority**

3. Receipt is acknowledged of papers submitted under 35 U.S.C. 119(a)-(d), which papers have been placed of record in the file.

# Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

- (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 4. Claims 1, 3, 16 and 19 are rejected under 35 U.S.C. 103(a) as being unpatentable over Nomoto et al., hereinafter "Nomoto" (U.S. Publication No. US 2002/0137288 A1) in view of Allman et al., hereinafter "Allman" (U.S. Publication US 2003/0157765).

Regarding claims 2, and 14, Nomoto discloses all the features of the claimed invention as discussed above, but does not disclose the plasma treatment is carried out over a duration of time of 40 seconds to 90 seconds.

Diodato, however, discloses the plasma treatment is carried out over a duration of time of 40 seconds to 90 seconds [col. 5, lines 61-65].

It would have been obvious to one having ordinary skilled in the art at the time the invention was made to modify the above discussed teaching of Nomoto as taught by Diodato for a purpose of improving a process of fabricating a semiconductor memory device.

Regarding claims 3, 8, 15 and 18, Diodato discloses after the formation of the charge storage film, a step of forming a contact hole (67, Fig. 8) through which a wiring connection (12-13, Fig. 8) is to be established, and then subjecting said film to the hydrogen plasma treatment through the contact hole (col. 6, lines 1+).

It would have been obvious to one having ordinary skilled in the art at the time the invention was made to modify the above discussed teaching of Nomoto as taught by Diodato for a purpose of improving a process of fabricating a semiconductor memory device.

Regarding claims 4 and 9, Diodato discloses plasma treatment is carried out before, during or after a barrier metal (Ti or TiN) is formed along the inner wall of the contact hole 67 (col. 7, lines 31-39).

It would have been obvious to one having ordinary skilled in the art at the time the invention was made to modify the above discussed teaching of Nomoto as taught by Diodato for a purpose of improving a process of fabricating a semiconductor memory device.

Art Unit: 2818

Regarding claims 1 and 13, Nomoto discloses a method of fabricating a semiconductor memory device comprising the steps of:

forming a charge storage film (13, Fig. 4) for storing electric charge (see paragraph 0072); and

erasing electric charge stored in the charge storage film, wherein the charge storage film is any one of a silicon nitride film, a double-layered film comprising a silicon oxide film and a silicon nitride film, and a three-layered film comprising a silicon oxide films a silicon nitride film and a silicon oxide film (see paragraph 0056-0059).

Nomoto discloses all the features of the claimed invention as discussed above, but does not disclose the erasing electric charge stored in the charge storage film by subjecting the charge storage to hydrogen plasma treatment.

Allman, however, discloses the erasing electric charge stored in the charge storage film by subjecting the charge storage to hydrogen plasma treatment 9see paragraph 0017 and 0042).

It would have been obvious to one having ordinary skilled in the art at the time the invention was made to modify the above discussed teaching of Nomoto as taught by Allman for a purpose of improving the electric field of the charge storage film.

Regarding claims 16 and 19, Nomoto discloses the annealing is carried out at 400°C or above (see paragraph 0128).

5. Claims 2-6, 8-11, 14-15 and 18 are rejected under 35 U.S.C. 103(a) as being unpatentable over Nomoto and Allman in view of Diodato et al., hereinafter "Diodato" (U.S. Patent No. 6,794,694).

Art Unit: 2818

Regarding claims 5-6, 10-11, Diodato discloses the barrier metal has a thickness of 5 nm or less and the plasma treatment is carried out at 350-450°C (col. 7, lines 47-53).

It would have been obvious to one having ordinary skilled in the art at the time the invention was made to modify the above discussed teaching of Nomoto as taught by Diodato for a purpose of improving a process of fabricating a semiconductor memory device.

## Conclusion

- 6. Applicants are advised to cancel the non-elected claims 21-22 in response to the next Office action if the application is considered to be allowed.
- 7. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Phuc T. Dang whose telephone number is (571) 272-1776. The examiner can normally be reached on 8:00 am-5:00 pm.
- 8. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David C. Nelms can be reached on (571) 272-1787. The fax phone numbers for the organization where this application or proceeding is assigned are 571-273-8300 for regular communications and After Final communications.
- 9. Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0956.

Langgohur

Phuc T. Dang

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Primary Examiner

Art Unit 2818